

L Number	Hits	Search Text	DB	Time stamp
1	626	("low k" or "methyl doped silica" or "fluorinated silicon glass" or FSG) and (PECVD or "plasma enhanced chemical vapor deposition")	USPAT; EPO; JPO; IBM_TDB	2003/06/02 15:12
2	86	((("low k" or "methyl doped silica" or "fluorinated silicon glass" or FSG) and (PECVD or "plasma enhanced chemical vapor deposition") ) and power and ("methyl silane" or ("nitrous oxide" or "NO.sub.2"))	USPAT; EPO; JPO; IBM_TDB	2003/06/02 13:38
3	1		USPAT	2003/06/02 13:21
6	107	((("low k" or "methyl doped silica" or "fluorinated silicon glass" or FSG) and (PECVD or "plasma enhanced chemical vapor deposition") ) and ("methyl silane" or ("nitrous oxide" or "NO.sub.2"))	USPAT; EPO; JPO; IBM_TDB	2003/06/02 15:12
7	391	("low k" or "methyl doped silica" or "fluorinated silicon glass" or FSG) and (PECVD or "plasma enhanced chemical vapor deposition") and power	USPAT; EPO; JPO; IBM_TDB	2003/06/02 13:52
12	89	((("black diamond" or "methyl doped silica" or "low k") and (PECVD or "plasma enhanced chemical vapor deposition") ) and ("methyl silane" or ("nitrous oxide" or "NO.sub.2"))	USPAT; EPO; JPO; IBM_TDB	2003/06/02 15:05
13	37	((("black diamond" or "methyl doped silica" or "low k") and (PECVD or "plasma enhanced chemical vapor deposition") ) and "methyl silane"	USPAT; EPO; JPO; IBM_TDB	2003/06/02 15:06
11	506	("black diamond" or "methyl doped silica" or "low k") and (PECVD or "plasma enhanced chemical vapor deposition")	USPAT; EPO; JPO; IBM_TDB	2003/06/02 16:08
14	20	"low k" and "methyl silane" and ("nitrous oxide" or "NO.sub.2") and (helium or He) and (oxygen or "O.sub.2") and power	USPAT; EPO; JPO; IBM_TDB	2003/06/02 15:14
15	1		USPAT	2003/06/02 16:04
16	28	"black diamond" and (PECVD or "plasma enhanced chemical vapor deposition")	USPAT; EPO; JPO; IBM_TDB	2003/06/02 16:23
17	65	("black diamond" or "methyl doped silica") and (CVD or " chemical vapor deposition")	USPAT; EPO; JPO; IBM_TDB	2003/06/02 16:24